

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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METHOD AND APPARATUS FOR For: SUPERCRITICAL PROCESSING

OF A WORKPIECE

Group Art Unit: 1763 Examiner: Ram N. Kacker

#### TRANSMITTAL LETTER

162 North Wolfe Road Sunnyvale, California 94086 (408) 530-9700

Customer Number 28960

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Enclosed please find a request for consideration of information disclosure statements mailed March 16, 2001, October 30, 2002, October 1, 2003, and June 24, 2004 for filing with the U.S. Patent and Trademark Office. Also, attached are copies of the information disclosure statements as filed on the above dates.

The Commissioner is authorized to charge any additional fee or credit any overpayment to our Deposit Account No. 08-1275. An originally executed duplicate of this transmittal is enclosed for this purpose.

> Respectfully submitted, HAVERSTOCK & OWENS LLP

Dated:\_\_\_\_ October 5, 2004

Thomas B. Haverstock Reg. No.: 32,571

Attorneys for Applicants

CERTIFICATE OF MAILING (37 CFR§ 1.8(a))

I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to the: Commissioner for Patents, P.O. Box 1450 Alexandria, VA

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### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Maximilian A. Biberger et al.

Serial No.: 09/704,641

Filed: November 1, 2000

For:

METHOD AND APPARATUS FOR SUPERCRITICAL PROCESSING

OF A WORKPIECE

Group Art Unit: 1763

Examiner: Ram N. Kackar

REQUEST FOR CONSIDERATION OF INFORMATION DISCLOSURE

STATEMENTS MAILED March 16, 2001, October 30, 2002, and October 1, 2003, and ELECTRONICALLY FILED June 24,

2004

162 N. Wolfe Road Sunnyvale, CA 94086 (408) 530-9700

Customer No.: 28960

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

The Examiner has acknowledged all the information disclosure statements filed in this case except those (1) mailed on March 16, 2001, (2) mailed on October 30, 2002, (3) mailed on October 1, 2003, and (4) electronically filed on June 24, 2004 (EFS ID 63275). For the Examiner's convenience, the Applicants have enclosed a copy of (1) each of the mailed information disclosure statements with its accompanying Form PTO-1449 and stamped return postcard and (2) the Acknowledgment Receipt for the electronically filed IDS. The Applicants would greatly appreciate acknowledgment of these information disclosure statements by having the enclosed Forms PTO-1449 and the Acknowledgment Receipt initialed and returned.

Respectfully submitted,

HAVERSTOCK & OWENS LLP

Dated:

10-5-04

CERTIFICATE OF MAJLING (37 CFR§ 1.8(a))

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Attorneys for Applicants

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Attorney Docket No.: SSI-00700

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	) Group Art Unit:
Maximilian A. Biberger et al.	Examiner:
Serial No.: 09/704,641	TRANSMITTAL LETTER
Filed: November 1, 2000	) 260 Sheridan Avenue, Suite 420 ) Palo Alto, California 94306

METHOD AND APPARATUS FOR SUPERCRITICAL PROCESSING

Assistant Commissioner for Patents Washington, D.C. 20231

**OF A WORKPIECE** 

Sir:

For:

Enclosed please find an Information Disclosure Statement, and Form PTO-1449, including copies of the references contained thereon, for filing in the U.S. Patent and Trademark Office.

The Commissioner is hereby authorized to charge any additional fee or credit overpayment to our Deposit Account No. <u>08-1275</u>. An originally executed duplicate of this transmittal is enclosed for this purpose.

Respectfully submitted,

HAVERSTOCK & OWENS LLP

Dated: 3-14-01

Thomas B. Haverstock Reg. No.: 32,571

Attorneys for Applicants

CERTIFICATE OF MAILING (37 CFR § 1.8(a))

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HAVERSTOCK & OWENS (IP

- 1 -





In the Matter of The Application of:	DFile No.: SSI-OOTOO BY: TBHNR Maximilian A. Biberger Hall Due Date: It and Trademark Office on the date stamped hereon:
□ Design Patent Application Pages □ Form PTO □ Utility patent Application Pages □ Form PTO □ Prov. Patent Application Pages □ Form PTO □ Declaration/Oath □ Maintenant □ Power of Attorney □ Reexamina □ Assignment □ Notice of AffidavirOr □ Small Entity Declaration □ Copy of Fi □ Drawings: Sheet(s) □ Req. for C	-1533 (Not. of Missing Parts) L-85B (issue Fee Trans) & dup1050 (Cert. of Correction) cer Fee Transmittal Form ation Request uppeal celaration  Transmittal Letter Certificate of Mailing Certificate of Express Mailing Label No.: Check(s):  Certificate of Express Mailing Certif



#### THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Maximilian A. Biberger et al.

Serial No.: 09/704,641

Filed: November 1, 2000

For:

METHOD AND APPARATUS FOR

SUPERCRITICAL PROCESSING

OF A WORKPIECE

Group Art Unit:

Examiner:

INFORMATION DISCLOSURE - STATEMENT

260 Sheridan Avenue, Suite 420 Palo Alto, California 94306

(650)833-0160

Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

The citations listed below, copies attached, may be material to the examination of the above-identified application, and are therefore submitted in compliance with the duty of disclosure defined in 37 C.F.R. §§ 1.56 and 1.97. The Examiner is requested to make these citations of official record in this application.

Applicants have become aware of the following printed publications which may be material to the examination of this application:

- U.S. Patent No. 2,617,719;
- U.S. Patent No. 3,890,176;
- U.S. Patent No. 3,900,551;
- U.S. Patent No. 4,029,517;
- U.S. Patent No. 4,091,643;
- U.S. Patent No. 4,341,592;
- U.S. Patent No. 4,474,199;
- U.S. Patent No. 4,475,993;
- U.S. Patent No. 4,601,181;
- U.S. Patent No. 4,693,777;
- U.S. Patent No. 4,749,440;
- U.S. Patent No. 4,788,043;

CERTIFICATE OF MAILING (37 CFR § 1.8(a))

I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to the: Assistant Commissioner for Patents, Washington D.C. 20231

3/16/01 By BLOW DI

Attorney Docket No.: PATENT SSI-00700

- U.S. Patent No. 4,838,476;
- U.S. Patent No. 4,865,061;
- U.S. Patent No. 4,879,004;
- U.S. Patent No. 4,923,828;
- U.S. Patent No. 4,924,892;
- U.S. Patent No. 4,944,837;
- U.S. Patent No. 4,960,140;
- U.S. Patent No. 4,983,223;
- U.S. Patent No. 5,011,542;
- U.S. Patent No. 5,013,366;
- U.S. Patent No. 5,068,040;
- U.S. Patent No. 5,105,556;
- U.S. Patent No. 5,143,103;
- U.S. Patent No. 5,158,704;
- U.S. Patent No. 5,174,917;
- U.S. Patent No. 5,185,058;
- U.S. Patent No. 5,185,296;
- U.S. Patent No. 5,193,560;
- U.S. Patent No. 5,213,619;
- U.S. Patent No. 5,215,592;
- U.S. Patent No. 5,225,173;
- U.S. Patent No. 5,236,602;
- U.S. Patent No. 5,237,824;
- U.S. Patent No. 5,261,965;
- U.S. Patent No. 5,266,205;
- U.S. Patent No. 5,267,455;
- U.S. Patent No. 5,274,129;
- U.S. Patent No. 5,288,333;
- U.S. Patent No. 5,290,361;
- U.S. Patent No. 5,294,261;
- U.S. Patent No. 5,304,515;
- U.S. Patent No. 5,306,350;
- U.S. Patent No. 5,313,965;

**PATENT** 

Attorney Docket No.: SSI-00700

- U.S. Patent No. 5,316,591;
- U.S. Patent No. 5,334,332;
- U.S. Patent No. 5,334,493;
- U.S. Patent No. 5,337,446;
- U.S. Patent No. 5,352,327;
- U.S. Patent No. 5,355,901;
- U.S. Patent No. 5,356,538;
- U.S. Patent No. 5,368,171;
- U.S. Patent No. 5,370,740;
- U.S. Patent No. 5,377,705;
- U.S. Patent No. 5,401,322;
- U.S. Patent No. 5,403,621;
- U.S. Patent No. 5,417,768;
- U.S. Patent No. 5,456,759;
- U.S. Patent No. 5,470,393;
- U.S. Patent No. 5,482,564;
- U.S. Patent No. 5,494,526;
- U.S. Patent No. 5,500,081;
- U.S. Patent No. 5,501,761;
- U.S. Patent No. 5,514,220;
- U.S. Patent No. 5,522,938;
- U.S. Patent No. 5,526,834;
- U.S. Patent No. 5,533,538;
- U.S. Patent No. 5,547,774;
- U.S. Patent No. 5,550,211;
- U.S. Patent No. 5,580,846;
- U.S. Patent No. 5,589,105;
- U.S. Patent No. 5,632,847;
- U.S. Patent No. 5,635,463;
- U.S. Patent No. 5,637,151;
- U.S. Patent No. 5,641,887;
- U.S. Patent No. 5,656,097;
- U.S. Patent No. 5,665,527;

- U.S. Patent No. 5,679,169;
- U.S. Patent No. 5,679,171;
- U.S. Patent No. 5,683,977;
- U.S. Patent No. 5,688,879;
- U.S. Patent No. 5,700,379;
- U.S. Patent No. 5,726,211;
- U.S. Patent No. 5,739,223;
- U.S. Patent No. 5,783,082;
- U.S. Patent No. 5,798,438;
- U.S. Patent No. 5,804,607;
- U.S. Patent No. 5,868,856;
- U.S. Patent No. 5,868,862;
- U.S. Patent No. 5,872,257;
- U.S. Patent No. 5,873,948;
- U.S. Patent No. 5,881,577;
- U.S. Patent No. 5,908,510;
- U.S. Patent No. 5,944,996;
- U.S. Patent No. 5,976,264;
- U.S. Patent No. 5,980,648;
- U.S. Patent No. 6,017,820;
- U.S. Patent No. 6,024,801;
- European Publication No. EP 0 726 099 A2;
- European Publication No. EP 0 587 168 A1;
- European Publication No. EP 0 572 913 A1;
- European Publication No. EP 0 536 752 A2;
- European Publication No. EP 0 283 740 A2;
- European Publication No. EP 0 302 345 A2;
- European Publication No. EP 0 370 233 A1;
- European Publication No. EP 0 391 395;
- Japanese Patent Abstract JP 2-304941;
- Japanese Patent Abstract JP 727711;
- Japanese Patent Abstract JP 1045131;
- Japanese Patent Abstract JP 2-148841;

Attorney Docket No.: <u>PATENT</u> SSI-00700

- Japanese Patent Abstract JP 7142333;
- Japanese Patent Abstract JP 8222508;
- Japanese Patent Abstract JP 60-192333;
- Japanese Patent Abstract JP 62-125619;
- PCT Publication No. WO 90/06189;
- PCT Publication No. WO 90/13675;
- Guan, Z. et al., "Fluorocarbon-Based Heterophase Polymeric Materials. 1. Block Copolymer Surfactants for Carbon Dioxide Applications," Macromolecules, Vol. 27, 1994, pp. 5527-5532.;
- International Journal of Environmentally Conscious Design & Manufacturing,
   Vol. 2, No. 1993, p. 83.;
- Journal of the American Ceramic Society, Vol. 72, No. 6, pp. 872-874.;
- Ziger, D.H. et al., "Compressed Fluid Technology: Application to RIE Developed Resists," AIChE Journal, Vol. 33, No. 10, October 1987, pp. 1585-1591.;
- Kirk-Othmer, "Encyclopedia of Chemical Terminology," 3<sup>rd</sup> ed., Supplement Volume, "Alcohol Fuels to Toxicology," 1984, pp. 872-893.;
- "Cleaning with Supercritical CO<sub>2</sub>," NASA Tech Brief, MFS-29611, Marshall Space Flight Center, Alabama, March 1979.;
- Basta, N., "Supercritical Fluids: Still Seeking Acceptance," Chemical Engineering, Vol. 92, No. 3, 2/24/85, 14.;
- Takahashi, D., "Los Alomos Lab finds way to cut chip toxic waste," Wall Street Journal, June 22, 1998;
- "Supercritical CO<sub>2</sub> process offers less mess from semiconductor plants, Chemical Engineering Magazine, pp 27 & 29, July 1998;
- Sun, Y.P. et al., "Preparation of polymer-protected semiconductor nanoparticles through the rapid expansion of supercritical fluid solution," Chemical Physics Letters, pp 585-588, May, 22, 1998;
- Jackson, K. et al., "Surfactants and Microemulsions in Supercritical Fluids" in "Supercritical Fluid Cleaning," Noyes Publications, Westwood, NJ, pp 87-120, Spring 1998;
- Kryszewski, M., "Production of Metal and Semiconductor Nanoparticles in Polymer Systems," Polymeri, pp 65-73, February 1998;

 Bakker, G.L. et al., "Surface Cleaning and Carbonaceous Film Removal Using High Pressure, High Temperature Water, and Water/CO<sub>2</sub> Mixtures," J. Eletrochem. Soc, Vol. 145, No. 1, pp 284-291, Jan. 98;

- Ober, C.K. et al., "Imaging polymers with supercritical carbon dioxide,"
   Advanced Materials, Vol. 9, No. 13, pp 1039-1043, 3 Nov 1997;
- Russick, E.M. et al., "Supercritical carbon dioxide extraction of solvent from micromachined structures," Supercritical Fluids -- Extraction and Pollution Prevention, ACS Symposium Series, Vol. 670, pp 255-269, 21 Oct 1997;
- Dahmen, N. et al., "Supercritical fluid extraction of grinding and metal cutting waste contaminated with oils," Supercritical Fluids -- Extraction and Pollution Prevention, ACS Symposium Series, Vol. 670, pp 270-279, 21 Oct 1997;
- Wai, C.M., "Supercritical fluid extraction: metals as complexes," J.
   Chromatograhy A, Vol. 785, PP 369-383, 17 Oct 1997;
- Xu, C. et al., Submicron-sized spherical yttrium oxide based phosphors prepared by supercritical CO<sub>2</sub>-assisted aerosolization and pyrolysis," Appl. Phys. Lett., Vol. 71, No. 12, September 22, 1997;
- Tomioka, Y. et al., "Decomposition of tetramethylammonium (TMA) in a positive photoresist developer by supercritical water," Abstracts of Papers 214th ACS Natl Meeting, American Chemical Society, Abstract no. 108, September 7, 1997;
- Klein, H. et al., "Cyclic organic carbonates serve as solvents and reactive diluents," Coatings World, pp 38-40, May 1997;
- Buhler, J. et al., Liner array of complementary metal oxide semiconductor doublepass metal micromirrors," Opt. Eng., Vol. 36, No. 5, pp 1391-1398, May 1997;
- Jo, M.H. et al., "Evaluation of SiO<sub>2</sub> aerogel thin film with ultra low dielectric constant as an intermetal dielectric, Microelectronic Engineering, Vol. 33, pp 343-348, Jan 1997;
- McClain, J.B. et al., "Design of nonionic surfactants for supercritical carbon dioxide," Science, Vol. 27, Dec. 20, 1996;
- Znaidi, L. et al., "Batch and semi-continuous synthesis of magnesium oxide powders from hydrolysis and supercritical treatment of Mg(OCH<sub>3</sub>)<sub>2</sub>," Materials Research Bulletin, Vol. 31, No. 12, pp 1527-1535, Dec 1996;
- Tadros, M.E., "Synthesis of titanium dioxide particles in supercritical CO<sub>2</sub>," J. Supercritical Fluids, Vol. 9, No. 3, pp 172-176, Sept 1996;

- Courtecuisse, V.G. et al., "Kinetics of the titanium isopropoxide decomposition in supercritical isopropyl alcohol," Ind. Eng. Chem. Res., vol 35, No. 8, pp 2539-2545, Aug 1996;
- Gabor, A. et al., "Block and random copolymer resists designed for 193 nm lithography and environmentally friendly supercritical CO<sub>2</sub> development," Dept. Mat. Sci. & Eng. Cornell Univ., SPIE, Vol. 2724, pp 410-417, Jun. 1996;
- Schimek, G.L. et al., "Supercritical ammonium synthesis and characterization of four new alkali metal silver antimony sulfides...," J. Solid State Chemistry, Vol. 123, pp 277-284, May 1996;
- Gallagher-Wetmore, P. et al., "Supercritical fluid processing: Opportunities for new resist materials and processes," IBM research Division, SPIE, Vol. 2725, pp 289-299, April 1996;
- Papathomas, K.I. et al., "Debonding of photoresists by organic solvents," J.
   Applied Polymer Science, Vol. 59, pp 2029-2037, Mar 28, 1996;
- Watkins, J.J. et al., "Polymer/metal nanocomposite synthesis in supercritical CO<sub>2</sub>," Chemistry of Materials, Vol. 7, no. 11, November 1995;
- Gloyna, E.F. et al., "Supercritical water oxidation research and development update," Environmental Progress, Vol. 14, No. 3, pp 182-192, August 1995;
- Gallagher-Wetmore, P. et al., "Supercritical fluid processing: A new dry technique for photoresist developing, IBM Research Division, SPIE, Vol. 2438, pp694-708, Jun. 1995;
- Gabor, A.H. et al., "Silicon-containing block copolymer resist materials,"
   Microelectronics Technology -- Polymers for Advanced Imaging and Packaging,
   ACS Symposium Series, Vol. 614, pp 281-298, April 1995;
- Tsiartas, P.C. et al., "Effect of molecular weight distribution on the dissolution properties of novolac blends," SPIE, Vol. 2438, pp 261-271, 1995;
- Allen, R.D. et al., "Performance properties of near-monodisperse novolak resins,"
   SPIE, Vol. 2438, pp 250-260, 1995;
- Wood, P.T. et al., "Synthesis of new channeled structures in supercritical amines...," Inorg. Chem., Vol. 33, pp 1556-1558, 1994;
- Jerome, J.E. et al., "Synthesis of new low-dimensional quaternary compounds...,"
   Inorg. Chem., Vol. 33, pp 1733-1734, 1994;

- McHardy, J. et al., "Progress in supercritical CO<sub>2</sub> cleaning," SAMPE Jour., Vol. 29, No. 5, pp 20-27, September 1993;
- Purtell, R. et al., "Precision parts cleaning using supercritical fluids," J. Vac. Sci. Technol. A, Vol. 11, No. 4, July 1993;
- Bok, E. et al., "Supercritical fluids for single wafer cleaning," Solid State
   Technology, pp 117-120, June 1992;
- Adschiri, T. et al., "Rapid and continuous hydrothermal crystallization of metal oxide particles in supercritical water," J. Am. Ceram. Soc., Vol. 75, No. 4, pp 1019-1022, 1992;
- Hansen, B.N. et al., "Supercritical fluid transport -- chemical deposition of films,"
   Chem. Mater., Vol. 4, No. 4, pp 749-752, 1992;
- Page, S.H. et al., "Predictability and effect of phase behavior of CO₂/propylene carbonate in supercritical fluid chromatography," J. Microl. Sep, Vol 3, No. 4, pp 355-369, 1991;
- Brokamp, T. et al., "Synthese und Kristallstruktur eines gemischtvalenten Lithium--Tantalnirids Li<sub>2</sub>Ta<sub>3</sub>N<sub>5</sub>," J. Alloys and Compounds, Vol. 176, pp 47-60, 1991;
- Hybertson, B.M. et al., "Deposition of palladium films by a novel supercritical fluid transport-chemical deposition process," Mat. Res. Bull., Vol. 26, pp 1127-1133, 1991;
- Ziger, D.H. et al., "Compressed fluid technology: Application to RIE-developed resists," AIChE Jour., Vol. 33, No. 10, pp 1585-1591, October 1987;
- Matson, D.W. et al., "Rapid expansion of supercritical fluid solutions: Solute formation of powders, thin films, and fibers," Ind. Eng. Chem. Res., Vol. 26, No. 11, pp 2298-2306, 1987;
- Tolley, W.K. et al., "Stripping organics from metal and mineral surfaces using supercritical fluids," Separation Science and Technology, Vol. 22, pp 1087-1101, 1987; and
- "Final report on the safety assessment of propylene carbonate," J. American College of Toxicology, Vol. 6, No. 1, pp 23-51.

 $\begin{array}{c} & \underline{PATENT} \\ Attorney \ Docket \ No.: \ \underline{SSI-00700} \end{array}$ 

This Information Disclosure Statement under 37 C.F.R. §§ 1.56 and 1.97 is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that anyone or more of these citations constitutes prior art.

Respectfully submitted,

HAVERSTOCK & OWENS LLP

Dated: 3-14-01

Thomas B. Haverstock Reg. No.: 32,571

**Attorneys for Applicants** 

FORM PTO-1449 Commerce (Modified)

U.S. Department of

Patent and Trademark Office

Attorney Docket No.: SSI-00700

Serial No.: 09/704,641

INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use Several Sheets If Necessary)

Applicant: Maximilian A. Biberger et al.

37 CFR § 1.98	8(b))			Filing Date: November 1, 2000 Group Art Unit:		it:	
г	<del></del>	Γ		U.S. PATENT DOCUMENTS	1		
Examiner Initials		Serial / Patent Number	Issue Date	Applicant / Patentee	Class	Subclass	Filing Dat
· -	AA	2,617,719	11/11/52	Stewart	23	312	12/29/50
	AB	3,890,176	06/17/75	Bolon	156	2	12/17/73
	AC	3,900,551	08/19/75	Bardoncelli et al.	423	9	03/02/72
	AD	4,029,517	06/14/77	Rand	134	11	03/01/76
	AE	4,091,643	05/30/78	Zucchini	68	18	02/17/77
	AF	4,341,592	07/27/82	Shories et al.	156	643	08/04/75
	AG	4,474,199	10/02/84	Blaudszun	134	105	11/09/82
	AH	4,475,993	10/09/84	Blander et al.	204	64T	08/15/83
	ΑI	4,601,181	07/22/86	Privat	68	18	11/17/83
	AJ	4,693,777	09/15/87	Hazano et al.	156	345	11/27/85
	AK	4,749,440	06/7/88	Blackwood et al.	156	646	05/12/87
	AL	4,788,043	11/29/88	Kagiyama et al.	422	292	04/17/86
	AM	4,838,476	06/13/89	Rahn	228	180.1	11/12/87
	AN	4,865,061	09/12/89	Fowler et al.	134	108	07/22/83
	AO	4,879,004	11/07/89	Oesch et al.	203	89	05/04/88
	AP	4,923,828	05/08/90	Gluck et al.	437	225	08/07/89
	AQ	4,924,892	05/15/90	Kiba et al.	134	123	07/28/88
	AR	4,944,837	07/31/90	Nishikawa et al.	156	646	02/28/89
	AS	4,960,140	10/02/90	Ishijima et al.	134	31	11/27/85
	ΑТ	4,983,223	01/08/91	Gessner	134	25.4	10/24/89
	AU	5,011,542	04/30/91	Weil	134	38	07/21/88
	ΑV	5,013,366	05/07/91	Jackson et al.	134	1	12/07/88
	AW	5,068,040	11/26/91	Jackson	210	748	04/03/89
	AX	5,105,556	04/21/92	Kurokawa et al.	34	12	08/09/88
	AY	5,143,103	09/01/92	Basso et al.	134	98.1	01/04/91
	AZ	5,158,704	10/27/92	Fulton et al.	252	309	07/25/90
	BA	5,174,917	12/29/92	Monzyk	252	60	07/19/91
	BB	5,185,058	02/09/93	Cathey, Jr.	156	656	01/29/91
	вс	5,185,296	02/09/93	Morita et al.	437	229	04/24/91
	BD	5,193,560	03/16/93	Tanaka et al.	134	56R	06/24/91
	BE	5,213,619	05/25/93	Jackson et al.	134	1	11/30/89
	BF	5,215,592	06/01/93	Jackson	134	1	01/22/91
	BG	5,225,173	07/06/93	Wai	423	2	10/25/91
	вн	5,236,602	08/17/93	Jackson	210	748	01/28/91
	BI	5,237,824	08/24/93	Pawliszyn	62	51.1	10/12/90
	BJ	5,261,965	11/16/93	Moslehi	134	1	08/28/92
aminer:				Date Considered:		•	

EXAMINER:

Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449 Commerce (Modified)

U.S. Department of

Patent and Trademark Office

INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use Several Sheets If Necessary)

(37 CFR & 1 98/b))

Attorney Docket No.: SSI-00700

Applicant: Maximilian A. Biberger et al.

Filing Date: November 1, 2000

Group Art Unit:

Serial No.: 09/704,641

		<del></del>		J.S. PATENT DOCUMENTS	<del></del>	<del></del> 1	
Examiner Initials		Serial / Patent Number	Issue Date	Applicant / Patentee	Class	Subclass	Filing Dat
	BK	5,266,205	11/30/93	Fulton et al.	210	639	07/01/92
	BL	5,267,455	12/07/93	Dewees et al.	68	5	07/13/92
	ВМ	5,274,129	12/28/93	Natale et al.	549	349	06/12/91
	BN	5,288,333	02/22/94	Tanaka et al.	134	ภ	07/29/92
	во	5,290,361	03/01/94	Hayashida et al.	134	2	01/23/92
	BP	5,294,261	03/15/94	McDermott et al.	134	7	11/02/92
	BQ	5,304,515	04/19/94	Morita et al.	437	231	08/07/92
	BR	5,306,350	04/26/94	Hoy et al.	134	22	04/27/92
	BS	5,313,965	05/24/94	Palen	134	61	06/01/92
	вт	5,316,591	05/31/94	Chao et al.	134	34	08/10/92
	BU	5,334,332	08/02/94	Lee	252	548	07/09/92
	BV	5,334,493	08/02/94	Fujita et al.	430	463	09/29/93
	вw	5,337,446	08/16/94	Smith et al.	15	21.1	10/27/92
	вх	5,352,327	10/04/94	Witowski	156	646	07/10/92
	BY	5,355,901	10/18/94	Mielnik et al.	134	105	10/27/92
	BZ	5,356,538	10/18/94	Wai et al.	210	634	10/21/9
	CA	5,368,171	11/29/94	Jackson	134	147	07/20/92
	СВ	5,370,740	12/06/94	Chao et al.	134	1	10/01/93
	СС	5,377,705	01/03/95	Smith, Jr. et al.	134	95.3	09/16/9:
	CD	5,401,322	03/28/95	Marshall	134	13	06/30/92
	CE	5,403,621	04/4/95	Jackson et al.	427	255.1	10/01/93
	CF	5,417,768	05/23/95	Smith, Jr. et al.	134	10	12/14/93
	CG	5,456,759	10/10/95	Stanford, Jr. et al.	134	1	08/01/94
	СН	5,470,393	11/28/95	Fukazawa	134	3	07/08/94
	CI	5,482,564	01/09/96	Douglas et al.	134	18	06/21/94
	CI	5,494,526	02/27/96	Paranjpe	134	1	05/04/9
	CK	5,500,081	03/19/96	Bergman	156	646.1	12/05/94
	CL	5,501,761	03/26/96	Evans et al.	156	344	10/18/94
	СМ	5,514,220	05/07/96	Wetmore et al.	134	22.18	12/09/93
	CN	5,522,938	06/04/96	O'Brien	134	1	08/08/9
	СО	5,526,834	06/18/96	Mielnik et al.	134	105	08/17/9
	СР	5,533,538	07/09/96	Marshall	134	104.4	12/01/9
	CQ	5,547,774	08/20/96	Gimzewski et al.	428	694	09/01/9
	CR	5,550,211	08/27/96	DeCrosta et al.	528	480	12/17/9
	CS	5,580,846	12/03/96	Hayashida et al.	510	175	01/09/9
	СТ	5,589,105	12/31/96	DeSimone et al.	252	351	05/18/95

EXAMINER:

Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449 (Modified)

U.S. Department of Commerce Patent and Trademark Office

Attorney Docket No.: SSI-00700

Serial No.: 09/704,641

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: Maximilian A. Biberger et al.

7 CFR § 1.9			ATEMENT BY APP If Necessary)		Filing Date: November 1, 2000 Group Art Unit			t:	
			1	U.S. PATENT DOC	CUMENTS				
Examiner Initials	Serial / Patent Issue Date		Applic	ant / Patentee	Class	Subclass	Filing	Date	
	CU	5,632,847	05/27/97	0	hno et al.	156	344	04/24	/95
	CV	5,635,463	06/03/97	Muraoka		510	175	07/19	/95
	CW	5,637,151	06/10/97		Schulz	134	2	06/27	/94
	CX	5,641,887	06/24/97	Bec	kman et al.	546	26.2	04/01	/94
	CY	5,656,097	08/12/97	Ol	esen et al.	134	1	12/21	/94
	CZ	5,665,527	09/09/97	A	llen et al.	430	325	02/03	/97
	DA	5,679,169	10/21/97	Gor	zales et al.	134	1.3	12/19	/95
	DB	5,679,171	10/21/97	S	aga et al.	134	3	03/06	i/96
	DC	5,683,977	11/04/97	Jureller et al.		510	286	03/06	i/95
	DD	5,688,879	11/18/97	DeSimone		526	89	02/17	1/97
	DE	5,700,379	12/23/97	Biebl		216	2	02/14	1/96
	DF	5,726,211	03/10/98	Hedrick et al.		521	61	03/21	i/96
	DG	5,739,223	04/14/98	D	eSimone	526	89 09/18/95		
· · · · · · · · · · · · · · · · · ·	DH	5,783,082	07/21/98	DeSimone et al.		210	634	11/03	3/95
	DI	5,798,438	08/25/98	Sawan et al.		528	483	09/09	)/96
	DJ	5,804,607	09/08/98	7/08/98 Hedrick et al.		521	64	10/10	5/97
	DK	5,868,856	02/09/99	Douglas et al.		134	2	07/2	3/97
	DL	5,868,862	02/09/99	Do	uglas et al.	134	134 26 07/31/97		
	DM	5,872,257	02/16/99	Вес	Beckman et al. 546 336		04/0	1/97	
	DN	5,873,948	02/23/99		Kim 134 19		06/24/97		
	DO	5,881,577	06/16/99	Sauer et al.  McCullough et al.		68	5	09/0	9/96
	DP	5,908,510	06/01/99			134	2	10/1	6/96
	DQ	5,944,996	08/31/99	DeSimone et al.		210	634	05/0	2/97
	DR	5,976,264	11/02/99	McC	ullough et al.	134	2	11/3	0/98
	DS	5,980,648	11/09/99		Adler	134	34	12/30	/93
	DT	6,017,820	01/25/00	1	Γing et al.	438	689	07/1	7/98
	DU	6,024,801	02/15/00	Wallace et al. 134 1		1	12/0	9/96	
			REIGN PATENTS O	OR PUBLISHED FO	REIGN PATENT APP	LICATIONS			
								Trans	lation
		Document Number	Publication Date	Country	y / Patent Office	Class	Subclass	Yes	N
····	DV	EP 0 726 099 A2	8/14/96		ЕРО	B08B	5/00		Х
	DW	EP 0587 168 A1	3/16/94		EPO	B08B	7/00		
	DX	EP 0 572 913 A1	12/8/93		EPO	B01D	11/02		,
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Attorney Docket No.: SSI-00700

Serial No.: 09/704,641

INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use Several Sheets If Necessary)

Applicant: Maximilian A. Biberger et al.

(37 CFR § 1	(Use Several Sheets If Necessary) 7 CFR § 1.98(b))				Filing Date: Novemb	er 1, 2000	Group Art Ur	uit:	
		FC	REIGN PATENTS (	OR PUBLISHED FOR	REIGN PATENT APPL	ICATIONS	r	т	
		Document	Publication Data	Country	/ Patent Office	Class	Subclass	Trans	lation
		Number	Publication Date	Country	/ Patent Office	Class	Suociass	Yes	No
	DY	EP 0 536 752 A2	4/14/93		ЕРО	C11D	3/20		х
	DZ	JP 2-304941	12/18/90		Japan	H01L	21/56		x
······································	EA	EP 0 283 740 A2	09/28/88		EPO	C22B	3/90		х
	ЕВ	EP 0 302 345 A2	02/08/89		ЕРО	C22B	3/00		х
	EC	EP 0 370 233 A1	05/30/90		EPO	C22B	3/00		X
	ED	EP 0 391 035	10/10/90		ЕРО	C23G	5/00		x
	EE	JP 727711	02/13/96		Japan	H01L	021/027		ļ
	EF	JP 1045131	02/17/89		Japan	B01D	011/04		
	EG	JP 2-148841	06/07/90		Japan	H01L	21/306		X
	ЕН	JP 7142333	06/02/95		Japan	H01L	021/027		
	EI	JP 8222508	08/30/96		Japan	H01L	021/027	ļ	
	EJ	JP 60-192333	09/30/85		Japan	H01L	21/30	X	
	EK	JP 62-125619	06/06/87		Japan	H01L	21/30		х
	EL	WO 90/06189	06/14/90		WIPO	B08B	7/00	ļ	X
	EM	WO 90/13675	11/15/90		WIPO	C22B	3/00	<u> </u>	Х
		OTHER	DOCUMENTS (Inclu	iding Author, Title, D	Date, Relevant Pages, Pla	ace of Publication)			
	EN	Guan, Z. et al., "F Applications," Mac	luorocarbon-Based He romolecules, Vol. 27	eterophase Polymeric , 1994, pp 5527-5532	Materials. 1. Block Co	opolymer Surfactan	ts for Carbon D	ioxide	
	EO	International Journa	ıl of Environmentally	Conscious Design &	Manufacturing, Vol. 2,	No. 1, 1993, p. 83	·		
	EP	Journal of the Ame	Journal of the American Ceramic Society, Vol. 72, No. 6, pp. 872-874.						
	EQ	Ziger, D.H. et al., 1987, pp 1585-159	Ziger, D.H. et al., "Compressed Fluid Technology: Application to RIE Developed Resists," AIChE Journal, Vol. 33, No. 10, October 1987, pp 1585-1591.						
	ER	Kirk-Othmer, "Enc	Kirk-Othmer, "Encyclopedia of Chemical Terminology," 3rd ed., Supplement Volume, "Alcohol Fuels to Toxicology," 1984, pp. 872-893.						
	ES	"Cleaning with Sup	"Cleaning with Supercritical CO2," NASA Tech Briefs, MFS-29611, Marshall Space Flight Center, Alabama, March 1979.						
	ET	Basta, N., "Superc	ritical Fluids: Still Se	eking Acceptance," (	Chemical Engineering, V	ol. 92, No. 3, 2/24	/85, 14		-
······	EU	Takahashi, D., "Lo	os Alomos Lab finds v	way to cut chip toxic	waste," Wall Street Jour	nal, June 22,1998.			
	EV				or plants, Chemical Eng				
·	EW	Sun, Y.P. et al., "I Chemical Physics I	Preparation of polyme etters, pp. 585-588,	er-protected semicond May 22, 1998.	uctor nanoparticles throu	igh the rapid expan	sion of supercri	tical fluid so	olution
	EX	Jackson, K. et al., Westwood, NJ, pp.	"Surfactants and Mic 87-120, Spring 1998	romulsions in Superci	ritical Fluids" in "Super	critical Fluid Clean	ing." Noyes Pu	blications,	
		1							

Kryszewski, M., "Production of Metal and Semiconductor Nanoparticles in Polymer Systems," Polymeri, pp. 65-73, February 1998

Bakker, G.L. et al., "Surface Cleaning and Carbonaceous Film Removal Using High Pressure, High Temperature Water, and Water/C02 Mixtures," J. Electrochem, Soc, Vol. 145, No. 1, pp. 284-291, Jan. 98.

Ober, C.K. et al., "Imaging polymers with supercritical carbon dioxide," Advanced Materials, Vol. 9, No. 13, 99. 1039-1043, 3 Nov 1997

Russick, E.M. et al., "Supercritical carbon dioxide extraction of solvent from micromachined structures." Supercritical Fluids Extraction and Pollution Prevention, ACS Symposium Series, Vol. 670, pp. 255-269,21 Oct 1997

Date Considered: Examiner:

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Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form **EXAMINER:** with next communication to applicant.

FC   Ext     FD   Wa     FE   Xu     FE   Xu     FF   To     FG   Kle     FH   Bul     FI   Jo     FI   Jo     FI   Mc     FI   Ta     FM   Co     FN   Ga     FN   Ga     FP   SP     FQ   Pa     FR   Wa     FT   Ga     FT   FT     FT   FT     FT   FT     FT   FT	Patent and Trademark Office ISCLOSURE STATEMENT BY APPLICANT se Several Sheets If Necessary)  OTHER DOCUMENTS (Including Author, Title, Description of Prevention, ACS Symposium Series, ai, C.M., "Supercritical fluid extraction: metals as complex as as a complex of the composition of tetramethylammonium pers 214th ACS Natl Meeting, American Chemical Society, ein, H. et al., "Decomposition of tetramethylammonium pers 214th ACS Natl Meeting, American Chemical Society, ein, H. et al., "Cyclic organic carbonates serve as solvents there, J. et al., Liner array of complementary metal oxide septically of the composition of SIO2 aerogel thin film with ulgineering, Vol. 33, pp. 343-348, Jan. 1997  Clain, J.B. et al., "Design of Nonionic Surfactants for suparical composition, which is a supercritical ammonium is propoxically," Materials Research Bulletin, Vol. 31, No. 12, dros, M.E., "Synthesis of titanium dioxide particles in supercrecuisse, V.G. et al., "Kinetics of the titanium isopropoxical 35, No. 8, pp. 2539-2545, Aug 1996  bor, A, et al., "Block and random copolymer resists design evelopment," Dept. Mat. Sci. & Eng. Cornell Univ., SPIE, himek, G. L. et al., "Supercritical ammonium synthesis and the Chemistry, Vol. 123 pp. 277-284, May 1996  llagher-Wetmore, P. et al., "Supercritical fluid processing: IE, Vol. 2725, pp. 289-299, April 1996.  pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical design of the control	and metal cutting waste contaminated with o Vol. 670, pp. 270-279, 21 Oct 1997  tes," J. Chromatograhy A, Vol. 785, pp. 369  phosphors prepared by supercritical CO2-ass  (TMA) in a positive photoresist developer by Abstract no. 108, September 7, 1997  and reactive diluents," Coatings Worlds, pp. emiconductor double-pass metal micromirror data low dielectric constant as an intermetal desercritical carbon dioxide," Science, Vol. 27, pp. 1527-1335, Dec. 1996  ercritical CO2" J. Supercritical Fluids, Vol. 1996  ercritical CO2" J. Supercritical Fluids, Vol. 1996  ded for 193 nm lithography and environmental Vol. 2724, pp. 410-417, Jun. 1995  d charaterization of four new alkali metal silves of the composition in supercritical metal silves opportunities for new resist materials and present the composition of the composition	9-383, 17 Oct 1997 sisted aerosolization and pyrolysis y supercritical water," Abstracts 38-40, May 1997 rs," Opt. Eng., Vol. 36, No.5, pp lielectric, Microelectronic , Dec. 20, 1996. supercritical treatment of 9, No. 3, pp.172-176, Sept 1996 alcohol, " ind. Eng. Chem. Res. lly friendly supercritical CO2 ver antimony sulfides," J. Solice
FC Da Ex PD Wa FE Ap FE Ap FI In	OTHER DOCUMENTS (Including Author, Title, Definition and Pollution Prevention, ACS Symposium Series, at, C.M., "Supercritical fluid extraction: metals as complex at, C. et al., Submicron-sized spherical yttrium oxide based ppl. Phys. Lett., Vol. 71, No.12, September 22, 1997 mioka Y, et al., "Decomposition of tetramethylammonium pers 214th ACS Natl Meeting, American Chemical Society, etc., H. et al., "Cyclic organic carbonates serve as solvents ther, J. et al., Liner array of complementary metal oxide sept-1398, May 1997  M.H. et al., "Evaluation of SIO2 aerogel thin film with ulgineering, Vol. 33, pp. 343-348, Jan. 1997  CClain, J.B. et al., "Design of Nonionic Surfactants for supadidi, L. et al., "Batch and semi-continous synthesis of maggiochia," Materials Research Bulletin, Vol. 31, No. 12, dros, M.E., "Synthesis of titanium dioxide particles in superurtecuisse, V.G. et al., "Kinetics of the titanium isopropox bor, A, et al., "Block and random copolymer resists design by the chemistry, Vol. 123 pp. 277-284, May 1996  llagher-Wetmore, P. et al., "Supercritical fluid processing: pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pathomas, K.J. et al., "Debonding of photoresists by organical pat	Date, Relevant Pages, Place of Publication) and metal cutting waste contaminated with o Vol. 670, pp. 270-279, 21 Oct 1997  tes," J. Chromatograhy A, Vol. 785, pp. 369 phosphors prepared by supercritical CO2-ass  (TMA) in a positive photoresist developer by Abstract no. 108, September 7, 1997  and reactive diluents," Coatings Worlds, pp. emiconductor double-pass metal micromirror stra low dielectric constant as an intermetal desercitical carbon dioxide," Science, Vol. 27, nesium oxide powders from hydrolysis and s pp. 1527-1335, Dec. 1996  ercritical CO2" J. Supercritical Fluids, Vol. dide decomposition in supercritical isopropylated for 193 nm lithography and environmental Vol. 2724, pp. 410-417, Jun. 1995  d charaterization of four new alkali metal silest opportunities for new resist materials and present the content of the proportunities for new resist materials and present the content of the proportunities for new resist materials and present the proportunities fo	poils, "Supercritical Fluids - 9-383, 17 Oct 1997 sisted aerosolization and pyrolysis by supercritical water," Abstracts 1. 38-40, May 1997 rs," Opt. Eng., Vol. 36, No.5, pp. dielectric, Microelectronic 1. Dec. 20, 1996. 1. Supercritical treatment of 1. No. 3, pp.172-176, Sept 1996 1. Supercritical treatment of 1. Sept. 1996 1. Supercritical CO2 1. Ver antimony sulfides," J. Solid
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FQ Pa 199 FR Wa 199 FS Gla Au  FT Ga SP FU Ga and FV Ts 27 FW All	pathomas, K.J. et al., "Debonding of photoresists by organ	<del></del>	processes," IBM research Division
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FS Gle Au  FT Ga  FU Ga  Ann  FV Ts:  FW All		ic solvents," J. Applied Polymer Science, V.	
FU Ga and FV Ts 27 FW All	atkins, J.J. et al., "Polymer/metal nanocomposite synthesis 95.	in supercritical CO2," Chemistry of Materia	als, Vol. 7, no. 11, November
FU Ga and FV Ts 27 FW All	oyna, E.F. et al., "Supercritical water oxidation research agust 1995	nd development update," Environment Progr	ess, Vol. 14, No. 3. Pp. 182-192
FV Ts 27 FW All	llagher-Wetmore, P. et al., "Supercritical fluid processing: IE Vol. 2438, pp.694-708, Jun. 1995	: A new dry technique for photoresist develo	ping, IBM Research Division,
FV Ts 27 FW All	abor, A. H. et al., "Silicon-containing block copolymer resid Packaging, ACS Symposium Series, Vol. 614, pp. 281-2	ist materials" Microelectronics Technology - 198, April 1995	Polymers for Advanced Imagin
FW All	iartas, P.C. et al., "Effect of molecular weight distribution 1, 1995		
FX We	len, R.D. et al., "Performance properties of near-monodisp		
	ood, P.T. et al., "Synthesis of new channeled structures in	supercritical amines," Inorg. Chem., Vol.	. 33, pp. 1556-1558, 1994
FY Jer	rome, J.E. et al., "Synthesis of new low-dimensional quater	rnary compounds," Inorg. Chem, Vol. 33,	, 1733-1734, 1994
FZ Mo	cHardy, J. et al., "Progress in supercritical CO2 cleaning,"	' SAMPE Jour., Vol. 29, No. 5, pp. 20-27,	September 1993
GA Pu	rtell, R, et al., "Precision parts cleaning using supercritical	l fluids, " J. Vac, Sci, Technol. A. Vol. 11,	No. 4, July 1993
	k, E, et al., "Supercritical fluids for single wafer cleaning,		
GC Ad	lschiri, T. et al., "Rapid and continuous hydrothermal cryst ol. 75, No. 4, pp. 1019-1022, 1992	tallization of metal oxide particles in supercr	ritical water," J. Am. Ceram. So
GD Ha	nsen, B.N. et al., "Supercritical fluid transport - chemical	deposition of films,"Chem. Mater., Vol. 4,	No. 4, pp, 749-752, 1992
GE Pa	ge, S.H. et al., "Predictability and effect of phase behavior	r of CO2/ propylene carbonate in supercritica	al fluid chromatography," J.
Examiner:	icrol. Sep, Vol 3, No. 4, pp. 355369, 1991	•	

FORM PTO-14 Commerce	49	U.S. Department of	Attorney Docket No.: SSI-00700	Serial No.: 09/704,641		
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		OTHER DOCUMENTS (Including Author, Title, I	Date, Relevant Pages, Place of Publication)			
	GF	Brokamp, T. et al., "Synthese und Kristallstruktur eines gemi 176. Pp. 47-60, 1991.	schivalenten Lithium-Tantainirids Li2Ta3N	s," J. Alloys and Compounds, Vol.		
	GG	Hybertson, B.M. et al., "Deposition of palladium films by a novel supercritical fluid transport chemical deposition process," Mat. Res. Bull., Vol. 26, pp. 1127-1133, 1991.				
	GH Ziger, D. H. et al., "Compressed fluid technology: Application to RIE-Developed resists," AiChE Jour., Vol. 33, No. 10, pp. 1585- 1591, October 1987.					
	GI Matson, D.W. et al., "Rapid expansion of supercritical fluid solutions: Solute formation of powders, thin films, and fibers," Ind. Eng. Chem. Res., Vol. 26, No. 11, pp. 2298-2306, 1987.					
	GJ Tolley, W.K. et al., "Stripping organics from metal and mineral surfaces using supercritical fluids," Separation Science and Technology, Vol. 22, pp. 1087-1101, 1987.					
	GK	"Final report on the safety assessment of propylene carbonate," J. American College of Toxicology, Vol. 6, No. 1, pp.23-51				
Examiner:			Date Considered:			
EXAMINER:	Ini wi	itial citation considered. Draw line through citation if not in con th next communication to applicant.	formance and not considered. Include copy	of this form		